



Synthesis of metal organic framework mesostructured UiO-66 with defections in frameworks for enhancing photocatalytic degradation of residues pesticides

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ABSTRACT

Novel photocatalysts, based on modified mesostructured UiO-66-Zr composites with defects sites in framework arrays were prepared by solvothermal synthesis method using CTABr as ionic surfactant template, acetic acid and benzoic acid as modulators. Modified UiO-66-Zr with defects sites in frameworks by using ionic surfactants CTABr, benzoic acid (UiO-66-M) and acetic acid (UiO-66-A) as modulators were synthesized, characterized by BET, XRD, FTIR, TEM, EDX techniques. The photocatalytic performances over material samples were tested in photodegradation of chlorpyrifos ethyl in aqueous solution under simulated solar light irradiation and evaluated by UV-Vis spectra combined with HPLC analysis. These modified UiO66 showed a highly effective photodegradation and mineralization of chlorpyrifos ethyl (pesticide/insecticide) in aqueous solution. The photocatalytic activities of the modified UiO66-Zr were considerably greater than unmodified UiO66-Zr composites were explained by the roles of defected sites created in material frameworks. The presence of the defects not only resulted in the dramatically enhanced porosity (pore size), but also induced the creation of Zr-OH groups which served as the main active adsorption sites for efficient ROS sequestration. The photodegradation rate of chlorpyrifos ethyl was ranked in the order of samples UiO66-Zr-M > UiO66-Zr-A > UiO66-Zr with reaction constant rate of $k_3 = 1.23 \times 10^{-2} \text{ (min}^{-1}\text{)} > k_2 = 9.1 \times 10^{-3} \text{ (min}^{-1}\text{)} > k_1 = 2 \times 10^{-4} \text{ (min}^{-1}\text{)}$, respectively. The obtained results showed potential application of modified UiO66-Zr composites for photocatalytic treatment of hydrophobic pesticide residues in water without any toxic secondary pollution in agriculture.

Introduction

Environmental agriculture pollutions by pesticides in soil, water, and air are affecting more adversely to

human life all over the world. Study on treatment and removal of pollution compounds, especially toxic organic compounds in aqueous solutions is thus important and urgent. Pesticide is a generic

term that covers a wide range of biologically-active compounds, including herbicides, fungicides and insecticides which were used in agricultures.^[1] Chlopyrifos ethyl have been used worldwide on a large scale in agriculture to control the growth of broad-leaved weeds on rice, maize, fruit vegetable and in post-emergence applications in most developing countries.^[1,2] There are many techniques to reduce and degradation of chlopyrifos residues, namely thermal desorption, biological method, photochemical catalysis, adsorption and liquid phase extraction.^[2] Among these methods, adsorption and photocatalysis methods have been widely studied due to low operating cost, easier of handling and high efficiency. Metal-organic frameworks (MOFs) are an emerging class of porous crystalline materials that consist of organic linkers and inorganic nodes. They have been widely studied due to their fundamental importance and versatile application potential, such as gas separation and catalysis, sensing devices, ion exchange, etc.^[2,5] Since finding out, great number of researches have been taken to tailor various aspects of MOF, including the introduction of functional groups to the linker, particle size control, attaching one or more metal cores into the framework, and engineering the number of missing linker and/or missing cluster defects. To be specific, the most hydrothermal stable metal-organic frameworks containing zirconium UiO-66 are crystal materials that consist of organic linkers H₂BDC and zirconium as inorganic nodes.^[4,5] UiO-66 crystals have large surface area but their pore size are small (1.5-2.5 nm) which limited in applications. The highly ordered mesoporous UiO66-Zr material was synthesis normally by using soft template as ionic surfactant (CTABr) [3]. Mesostructured UiO-66 possess uniform and large pore size, which enables bulky molecules to diffuse easily and contact with the active centers in the pore [3-7]. These materials can be also modified by creation defect sites (missing linker) in framework by using acetic acid and benzoic acid as modulators [8-10]. Due to their structure these materials can significantly facilitate the transfer of photocarriers and suppressed the recombination of photogenerated electrons/holes and increase quantum efficiency in photocatalytic degradation of organic pesticides such as hydrophobic Chlopyrifos ethyl [8-14].

In this study, we focused on synthesizing modified MOFs material with defects creation in mesoporous UiO66-Zr structure. The defects can narrow the band gap of UiO-66, and this is majority attributed to the density of unrecombination electron/hole pairs flow

under light irradiation. These modified MOFs material acts as novel photocatalyst that promotes the photo oxidation degradation of chlopyrifos ethyl in aqueous solution under irradiation of UV light and simulated solar light.

Experimental

Chemicals

Benzen-1,4-dicarbonylic acid (H₂BDC) (Sigma Aldrich, 99.5 %), Zirconyl chloride octahydrate (ZrOCl₂.8H₂O, Sigma Aldrich, 98 %), NN-dimethylformamide (DMF) (CH₃)₂NC(O)H, China, 99%), Hexadecyl-trimethyl-ammoniumbromide (CTABr) (H₃C-(CH₂)₁₅-N+(CH₃)₃ (Br-), Merck, 98 %), acetic acid (CH₃COOH, China, 99.5 %), Hydrochloric acid (HCl, China, 36.5 %), Sodium hydroxide (NaOH, China, 98 %), Benzoic acid (C₆H₅COOH, England) 98 %, toluene (C₆H₅CH₃, China, 99.5 %), ethanol (C₂H₅OH, China, 96 %) Methylene blue (Sigma Aldrich), Methanol (China), Chlopyrifos ethyl (99.95 %, Analysis trade standard from Sigma).

Preparation

Synthesis of modified UiO-66

Typical, ZrOCl₂.8H₂O (6.44 g), H₂BDC (3.32 g), 36 % HCl (5ml) were dissolved in 280 ml DMF with the assistance of ultrasonication for 30 minutes. Subsequently, the mix was transferred into a Teflon-autoclave, sealed and placed in a preheated oven at 120 °C for 24 hours. After cooling down to room temperature, the pre-precipitate was collected by centrifugation and washed with DMF three times. Then the solid was stirred in DMF at 363 K for 12 h, then in methanol at 333 K for 12 h to remove unreacted chemicals and solvent. The resulting white powder was dried under vacuum at 423 K for 12 h.

Synthesis of modified UiO-66 using acetic acid (UiO-66-Zr-A)

ZrOCl₂.8H₂O (2.00 g), 99.5 % acetic acid (40ml) was dissolved in 700 ml DMF, ultrasonicated for 30 minutes, heated at 130 °C for 2 hours. After that 7.5 g added of H₂BDC the mix was stirred for 18 hours at 25 °C. The resulting mix was filtered, washing several times, and

purified with DMF and ethanol for removal unreacted reactants, followed by drying for 24 hours at 120 °C.

Synthesis of modified mesostructured UiO-66 by ionic surfactant CTABr and benzoic acid (UiO-66-Zr-M)

ZrOCl₂·8H₂O (6.44 g), H₂BDC (3.32 g), benzoic acid (4.88 g), HCl (3.2 ml) were dissolved in 250 ml DMF. Subsequently, modulator CTABr (0.365 g) dissolved in 95 ml DMF was added to the mix, stirring until cleared solution obtained, then the mix was transferred in to a round bottomed flask 1000ml, which was attached the reflux condenser, heated at 120 °C for 24 hours with continuously stirring 300 rpm. After cooling down to room temperature, the pre-cipitate was collected by centrifugation and washed with DMF three times. Then the solid was stirred in DMF at 90 °C for 12 h, then in methanol at 70 °C for 12 h to remove unreacted chemicals and solvent. The resulting white powder was dried under vacuum at 150 °C for 12 h.

Characterizations

X-ray diffraction (XRD) data were recorded using a 8D Advance Bucker diffractometer with CuK α radiation, the scanning angle with a range of 1-50° 2 θ . The IR spectra were recorded from disk-membraned samples (1 %) in KBr pellets by IR spectra photometer. Nitrogen adsorption-desorption isotherms were measured at 77 K using a Micromeritics system after the samples were de-gassed at 200 °C for 4 h. The specific surface area, S_{BET}, was determined by the Brunauer-Emmett-Teller (BET) method, and the pore-diameter distribution was analyzed by the Barrett-Joyner-Halenda (BJH) method. Transmission electron micrographs (TEM) were obtained using a JEOL JEM 1230 microscope operating at 80 kV. Diffuse reflectance UV-Vis spectra was recorded in the range of 200-800 nm at room temperature by GBC Instrument-2885. Energy-dispersive X-ray spectroscopy (EDX). All characteristics of materials in this article were determined at Vietnam Academy of Science and Technology.

Photocatalytic degradation of Chlopyrifos ethyl under simulated sunlight

In each experiment using 30 mg material and 100ml of chlopyrifos ethyl (50 mg/L) solution were put in a glass vessel 250 ml volume, stirring at 600 rpm in dark for 60 minutes for absorption equilibrium. Then reactions mix was irradiated by Osram lamp Ultra-vitalux 300W (λ = 365-450 nm), keep continuously stirring and

taking liquid samples at 90, 120, 150, 180 and 240 minutes. Filtering liquid samples by filter for analysis by UV-Vis spectra at 229 nm.

Reaction constant

Assuming that photochemistry reaction is first- order reaction, reaction constant is calculated by this equation: $-\ln(C_t/C_0) = kt$; k - constant metabolic reaction rate; C₀ (mg/L): the initial concentrations of chlopyrifos ethyl; C_t (mg/L): the equilibrium concentrations of the adsorbate; V (L): the volume of reaction solution; m (g): the mass of the carrier; k (min⁻¹): reaction constant.

Results and Discussion

Characterifications of samples

The characteristic diffraction peaks at 2 θ ~ 6.5°, 8.5° are presented in UiO66, UiO66-A and UiO66-M samples, indicating the formation of crystals. Thus, the structure of UiO-66 is retained after the introduction of defects, in accordance with the XRD analysis. The XRD spectrum of the UiO-66-M sample are diffracted at the angles smaller than 1° which demonstrate the mesopore structure in comparison to UiO66 and UiO66-A. The characteristic peaks of H₂BDC at 17.4°, 25.4°, 28.1° do not appear, which means H₂BDC used in synthesizing process was removed completely.

The IR spectrum showed: the absorption band at frequencies of 1577-1580 cm⁻¹ and 1398 cm⁻¹ are associated with the OCO asymmetric and symmetric stretch vibrations of the carboxylate groups of the BDC linker.^[21] The absorption band at frequency of 1506 cm⁻¹ is characterizes the vibrations of the C=C bond within the aromatic ring of the BDC linker [21]. The absorption band with small intensity at the frequency of 746-489 cm⁻¹ characterizesthe vibrations of the Zr-O bonds. The absorption band at 1158-1017 cm⁻¹ characterizes the oscillation of the benzene ring. In addition, the absorption band at frequencies above 3400 cm⁻¹ characterizes water molecules in crystals and water molecules that are physically absorbed inside material pores.

From TEM images of samples UiO-66 (b), UiO-66-A (a), UiO-66-M (c) (Figure 2) it could be seen that UiO-66 no defects possessed cubic shape but UiO-66-A (Figure 2a) showed the crystals were damaged a little caused by acetic acid. While using ionic surface agent CTABr and benzoic acid in initial mix beside defects creations

but also mesoporous structures were formed in UiO-66-M. From the BET results, it can be see that only UiO-66-M plots have hysteresis loop at P/P₀ of 0.7 and 0.6 respectively that characterize for the existence of

meso size pores. Whereas, UiO-66, UiO-66-A plots do not have these characterizations due to the fact of these two materials just contain micropore only.

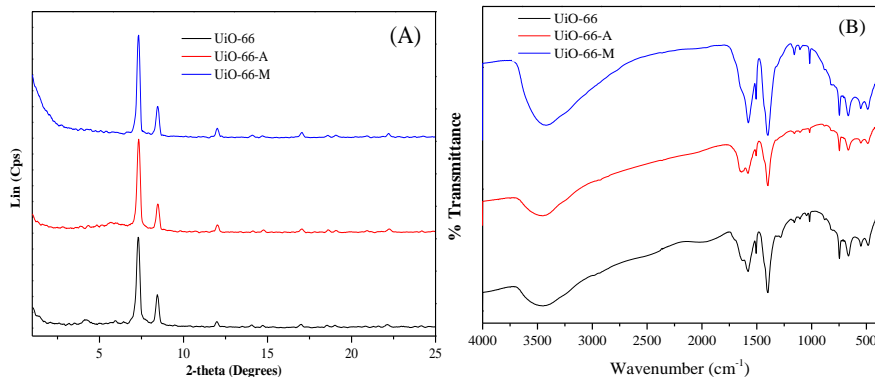


Figure 1: XRD of samples (A), IR of samples (B)

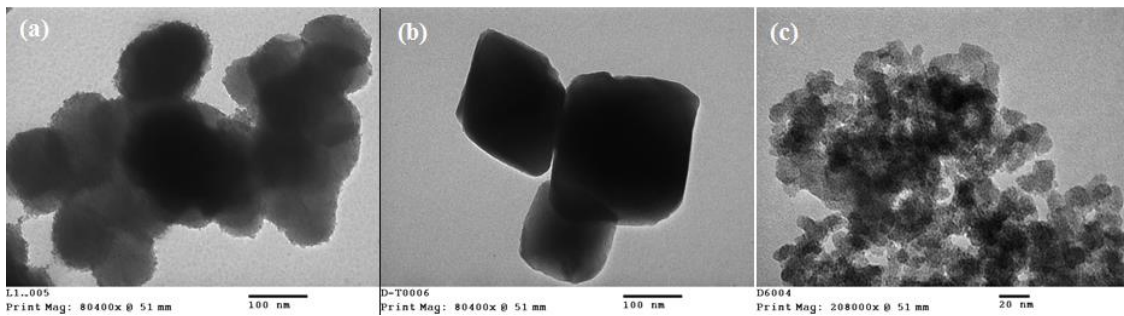


Figure 2: TEM images of samples UiO-66 (b), UiO-66-A (a), UiO-66-M (c)

Table 1: BET parameters of samples

Samples	Modified method	S _{BET} (m ² /g)	V _t (cm ³ /g)	d _{pore} (nm)
UiO-66	-	647	0.093	2.18
UiO-66-A	CH ₃ COOH	1890	0.153	3.09
UiO-66-M	C ₆ H ₅ COOH; CTABr	766	1.283	9.26

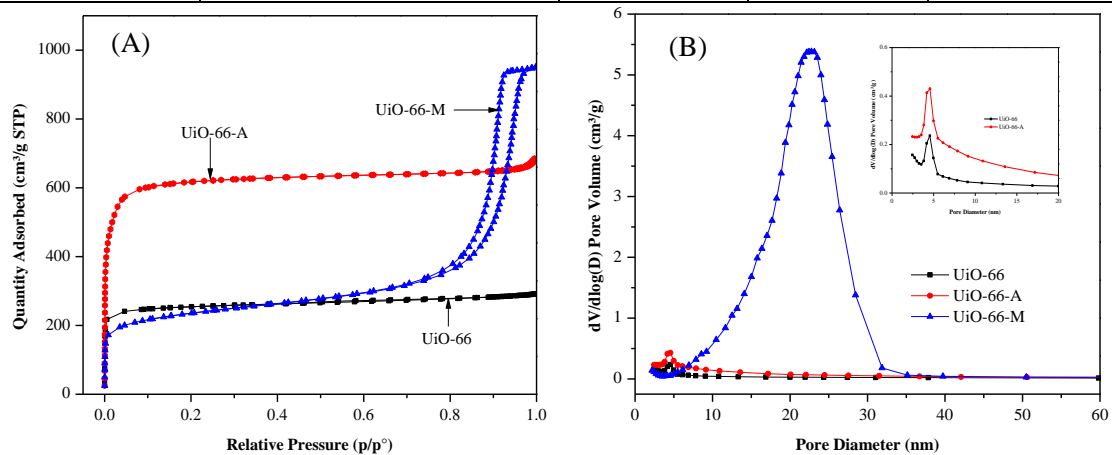


Figure 3: Isothermal adsorption/deadsorption nitrogen (A); and pores distribution (B) of samples UiO-66, UiO-66-A, UiO-66-M

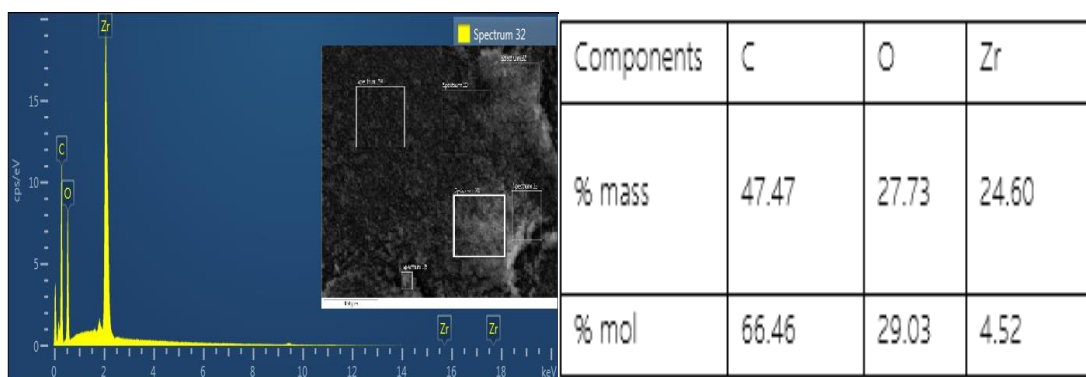


Figure 4: EDX and components analysis of UiO-66-M

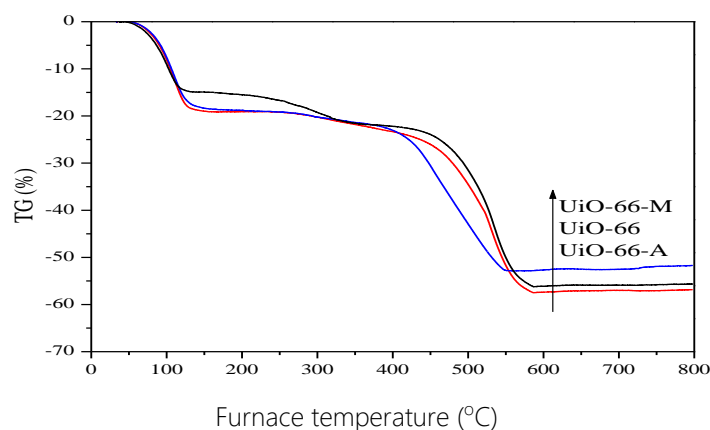


Figure 5: TGA results obtained of samples samples UiO-66, UiO-66-A, UiO-66-M

Besides that, the big difference in the pore size of UiO-66-M and UiO-66-A may stand for mesostructure of material. As our results, the creation of defects in UiO-66 framework does not guarantee the enhancement of the BET surface area but increases the pore size, especially intergration mesostructured modification by soft templating (Fig. 3). From TGA results obtained of defected samples it can be seen the thermal stability of the framework is reduced upon the generation of defects (Fig. 5). Both of defective UiO-66-A and UiO-66-M showed no improvement adsorption performance for Chlopyrifos because the surface area decreased (table 1). But the existence of supermicropores (UiO-66-A) and mesopores (UiO-66-A) created by linker missing, which allows more active sites accessible to probe molecules or charge change increased the photocatalytic degradation (Fig. 6). Defective UiO-66 UiO-66-A and UiO-66-M showed the rate constants of Photocatalytic degradation of Chlorpyrifos with $2 \times 10^{-4} \text{ min}^{-1}$ and $9.1 \times 10^{-3} \text{ min}^{-1}$ and $1.23 \times 10^{-2} \text{ min}^{-1}$ respectively (Fig 7). Such an improvement was mainly attributed to the pore

structure change and additional active sites caused by linker/cluster missing. The selectivity absorption and photocatalytic activities for decomposition of Chlopyrifos over defected UiO-66-M, UiO-66-A in compared to undefected UiO-66 (figure 6) were mainly caused by the charge change after defecting. It can be explained that when defects are created, especially cluster missing, large pores might be obtained (table 1). Thus exposing more active sites and facilitating diffusion of reactant species and enhance photocatalytic degradation of chlopyrifos can be explained by charge change, whereas the defective sites (missing linkers) playing as vacancy lattice sites, which are incorporated into framework, with stronger π - π bonding contributed to the improved light absorption and reduce the recombination of e^-/h^+ both in side and surface of particles materials.^[12] For that defected UiO-66 samples were enhanced Chlopyrifos photocatalytic degradation due to the strong inherent affinity of active site and the additional active sites that induced by the change of coordination number.

Absorption and photocatalytic degradation of chlorpyrifos ethyl in aqueous solution

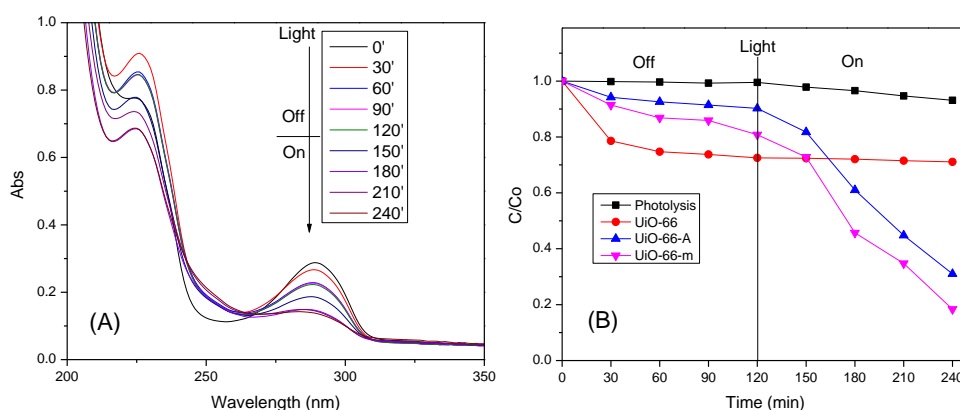


Figure 6: Photocatalytic degradation of Chlorpyrifos over samples UiO-66, UiO-66-A, UiO-66-M (B)

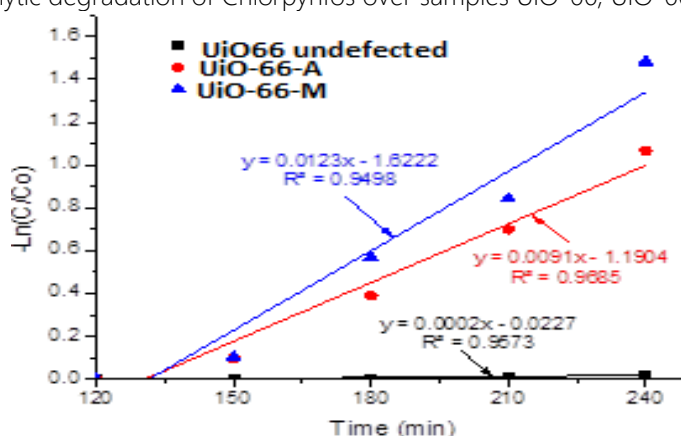


Figure 7: Rate constants of Photocatalytic degradation of Chlorpyrifos for UiO-66, UiO-66-A, UiO-66-M (B)

Table 3: Absorption capacity and photocatalytic degradation of chlorpyrifos ethyl in aqueous solution 240 minutes, simulated sunlight 880 mW/cm²

Samples	Conversion of Chlorpyrifos, % (for 240')	Rate constants of Photocatalytic degradation of Chlorpyrifos Chlorpyrifos (min ⁻¹)
UiO-66	28.92	2×10^{-4}
UiO-66-A	68.98	9.1×10^{-3}
UiO-66-M	81.65	1.23×10^{-2}

The results of the evaluations of the photodegradation performance of Chlorpyrifos ethyl by the HPLC method (Fig. 8) are also equivalent to the evaluation results of the UV-Vis method analysis (Fig. 6). After 240 min in

dark and under simulated sunlight irradiation Chlorpyrifos ethyl was decomposed 90 % to non-toxic inorganic with no intermediate compounds were presented as showed in the HPLC-MS spectrum.

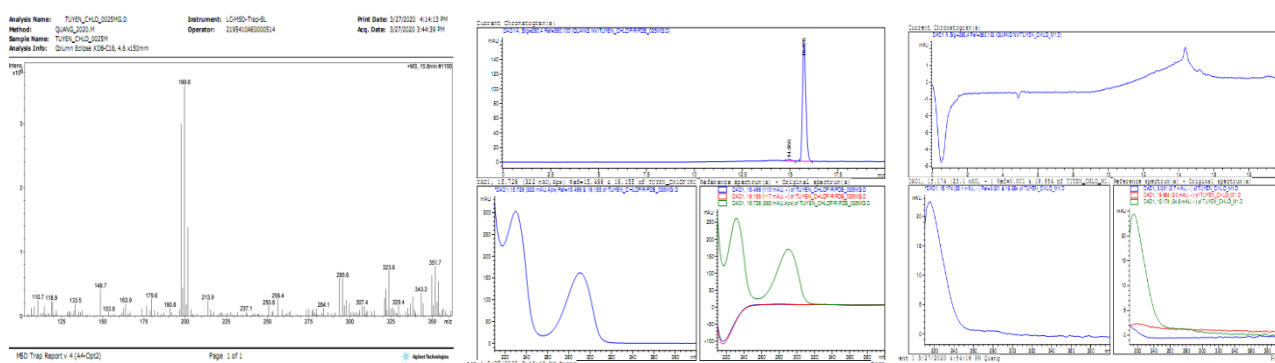


Figure 8: HPLC-MS spectrum of chlorpyrifos and degradation products over photocatalyst UiO-66-M

Conclusions

Successfully synthesized modified Metal Organic Framework UiO-66 (Zr) UiO-66, UiO-66-A and UiO-66-M with defects in material network by using surfactant template, acetic acid and benzoic acid as modulators. Defected UiO-66-A and UiO-66-M materials showed no improvement adsorption performance but the existence of supermicropores (UiO-66-A) and mesopores (UiO-66-M) created by linker missing, which allows more active sites accessible to probe molecules or charge change increased the photocatalytic degradation of chlpyrifos ethyl in water. The thermal stability of the framework is reduced upon the generation of defects. This is considered as a new point in the methods of synthesis MOFs in general, and also in particular methods of synthesis modified MOFs materials with defects creation combination with intergrated mesostructures, which enhance the photocatalytic degradation of hydrophobic pesticides residues under sun light in agriculture cultivation.

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